

<p>Case 1:449 (Modified)</p> <p>Information Disclosure Statement By Applicant</p>	<p>Atty Docket No. NOVLP037C1/ NVLS-000519C1</p> <p>Applicant: van Schravendijk et al.</p> <p>Filing Date February 5, 2004</p>	<p>Application No.: 10/773,821</p> <p>Group 2813</p>
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U.S. Patent Documents

[illegible]

Foreign Patent or Published Foreign Patent Application

[illegible]

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1	Li et al., "Methods of Forming Moisture Barrier for Low K Film Intergration with Anti-Reflective Layers", Novellus Systems, Inc., Appln. No. 11/168,013, filed June 27, 2005, pages 1-25. [NOVLP128/NVLS-3043]
	C2	U.S. Office Action mailed October 24, 2002, from U.S. Application No. 09/990,197. [NOVLP037/NVLS-000519]
	C3	U.S. Office Action mailed May 21, 2003, from U.S. Application No. 09/990,197. [NOVLP037/NVLS-000519]

Examiner	Date Considered 12/16/05
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.